

**IN THE CLAIMS:**

Please amend the claims as follows:

1.     **(Currently Amended)**     A substrate processing apparatus comprising:  
  
a chamber having a container and [a] an upper lid for closing an opening of the container, wherein the upper lid includes an electron beam irradiating part disposed in a center thereof; and  
  
an elevator for moving the upper lid, disposed integrally with the chamber.
2.     **(Original)**     A substrate processing apparatus according to claim 1, wherein the opening is provided on top of the container; and  
  
wherein the elevator is disposed on an upper side of the chamber.
3.     **(Original)**     A substrate processing apparatus according to claim 2, wherein the elevator has:  
  
a first pole erected from an upper side of the container so as to extend vertically;  
  
a driving source, attached to the upper lid, for outputting a predetermined turning force; and  
  
a power converting mechanism for converting the turning force outputted from the driving source into a vertical force for vertically moving the upper lid along the first pole.
4.     **(Original)**     A substrate processing apparatus according to claim 3, wherein the power converting mechanism includes:  
  
a first tubular member inserted onto the first pole and held by the upper lid so as to be rotatable about the first pole;  
  
a first thread provided on an inner face of the first tubular member; and

a second thread provided on a surface of the first pole and adapted to engage the first thread.

5. **(Original)** A substrate processing apparatus according to claim 4, wherein the elevator further has:

a second pole erected from the upper side of the container so as to extend vertically;

a second tubular member inserted onto the second pole and held by the upper lid so as to be rotatable about the second pole;

a third thread provided on an inner face of the second tubular member;

a fourth thread provided on a surface of the second pole and adapted to engage the third thread; and

a power transmitting mechanism, disposed between the first and second tubular members, for rotating the second tubular member in synchronization with the first tubular member.

6. **(Original)** A substrate processing apparatus according to claim 3, further comprising a tubular cover detachably attached to the first pole so as to cover the surface of the first pole.

7. **(Currently Amended)** A substrate processing apparatus according to claim 1, wherein the chamber ~~has~~: further comprises a substrate holding part for positioning and holding a substrate[:]; and wherein the [an] electron beam irradiating part ~~for irradiating~~ irradiates the substrate with an electron beam.

8. **(Currently Amended)** A maintenance method for a substrate processing apparatus having a chamber including a container and an upper lid for closing an upper opening of the container, wherein the lid includes an electron beam irradiating part disposed in a center thereof, the method comprising the step of:

vertically raising the upper lid and carrying out maintenance within the container while the upper lid is held at a position separated by a predetermined distance from above the container.